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 APPLICATION NO.
 FILING DATE
 FIRST NAMED INVENTOR
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 09/882, 141
 06/15/01
 WANG
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 AM1562D1

IM52/1012

EXAMINER

PATENT COUNSEL APPLIED MATERIÁLS, INC PO BOX 450A SANTA CLARA CA 95052

UMEZ ERONINI, L

ARTUNIT PAPER NUMBER

1765

DATE MAILED: 10/12/01

Please find below and/or attached an Office communication concerning this application or proceeding.

Commissioner of Patents and Trademarks

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	,	Application No.	Applicant(s)
· Office Astion Commons		09/882,141	WANG ET AL.
ار	Office Action Summary	Examiner	Art Unit
		Lynette T. Umez-Eronini	1765
The MAILING DATE of this communication appears on the cover sheet with the correspondence address Period for Reply			
A SHORTENED STATUTORY PERIOD FOR REPLY IS SET TO EXPIRE 3 MONTH(S) FROM THE MAILING DATE OF THIS COMMUNICATION. - Extensions of time may be available under the provisions of 37 CFR 1.136(a). In no event, however, may a reply be timely filed after SIX (6) MONTHS from the mailing date of this communication. - If the period for reply specified above is less than thirty (30) days, a reply within the statutory minimum of thirty (30) days will be considered timely. - If NO period for reply is specified above, the maximum statutory period will apply and will expire SIX (6) MONTHS from the mailing date of this communication. - Failure to reply within the set or extended period for reply will, by statute, cause the application to become ABANDONED (35 U.S.C. § 133). - Any reply received by the Office later than three months after the mailing date of this communication, even if timely filed, may reduce any earned patent term adjustment. See 37 CFR 1.704(b).			
Status			
1)[Responsive to communication(s) filed on		
2a) <u></u> □	,—	s action is non-final.	
3) Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under <i>Ex parte Quayle</i> , 1935 C.D. 11, 453 O.G. 213.			
Disposition of Claims			
4)⊠ Claim(s) <u>1-6</u> is/are pending in the application.			
4a) Of the above claim(s) is/are withdrawn from consideration.			
5) Claim(s) is/are allowed.			
6)⊠ Claim(s) <u>1-3,5 and 6</u> is/are rejected.			
7) Claim(s) <u>4</u> is/are objected to.			
8) Claim(s) are subject to restriction and/or election requirement.			
Application Papers			
9) The specification is objected to by the Examiner.			
10) The drawing(s) filed on is/are: a) accepted or b) objected to by the Examiner.			
Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).			
11) The proposed drawing correction filed on is: a) □ approved b) □ disapproved by the Examiner.			
If approved, corrected drawings are required in reply to this Office action.			
12) ☐ The oath or declaration is objected to by the Examiner.			
Priority under 35 U.S.C. §§ 119 and 120			
13) Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f).			
a) ☐ All b) ☐ Some * c) ☐ None of:			
1. Certified copies of the priority documents have been received.			
2. Certified copies of the priority documents have been received in Application No			
 3. Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)). * See the attached detailed Office action for a list of the certified copies not received. 			
14) Acknowledgment is made of a claim for domestic priority under 35 U.S.C. § 119(e) (to a provisional application).			
a) The translation of the foreign language provisional application has been received. 15) Acknowledgment is made of a claim for domestic priority under 35 U.S.C. §§ 120 and/or 121.			
Attachment(s)			
1) Notice	e of References Cited (PTO-892) e of Draftsperson's Patent Drawing Review (PTO-948) nation Disclosure Statement(s) (PTO-1449) Paper No(s) 3.		(PTO-413) Paper No(s) Patent Application (PTO-152)
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DETAILED ACTION

Claim Rejections - 35 USC § 112

1. The following is a quotation of the second paragraph of 35 U.S.C. 112:

The specification shall conclude with one or more claims particularly pointing out and distinctly claiming the subject matter which the applicant regards as his invention.

2. Claim 1 is rejected under 35 U.S.C. 112, second paragraph, as being indefinite for failing to particularly point out and distinctly claim the subject matter which applicant regards as the invention.

In claim 1, lines 2 and 3, "a fluorine-containing gas selected from the group consisting of SF_6 , Si_2F_6 and SiF_4 , together with HBr and oxygen, is indefinite because it is unclear which gas combination is required by the claim. Does the claim require for example

A SF₆, HBr and O₂;

B Si₂F₆, HBr and O₂;

C SiF₄, HBr and O₂; or

A₁ SF₆

B₁ Si₂F₆

C₁ SiF₄, HBr and O₂

Claim Rejections - 35 USC § 102

3. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

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4. Claims 1-3 are rejected under 35 U.S.C. 102(b) as anticipated by or, in the alternative, under 35 U.S.C. 103(a) as obvious over Komura et al. (US 5,423,941).

Komura teaches etching a silicon semiconductor substrate with an etchant gas mixture comprising HBr, SiF₄, He, O₂, and SF₆ (Figure 1A; column 4 line 23-27; column 6, lines 49-52, 63-66; Tables 1, 2, 3, and 6; Figure 3; and column 4, lines 8-24). Komura's etchant mixture is the same as the claimed etch mixture consisting essentially of a fluorine-containing gas selected from the group consisting of SF₆, Si₂F₆, SiF₄, together with HBr, and oxygen. O₂.

Claim Rejections - 35 USC § 103

- 5. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
 - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 6. Claims 5 and 6 are rejected under 35 U.S.C. 103(a) as being unpatentable over Komura '941) as applied to claim 1 above.

Komura differs only in failing to specify recited processing variables such as the volume ratio of HBr:SF₆ of 0.1 to 10, in claim 5 and HBr and SF₆:O₂ of 0.1 to 10, in claim 6.

It would have been obvious to one having ordinary skill in the art at the time of the claimed invention to employ any of a variety of processing variables such as those Application/Control Number: 09/882,141

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claimed by the applicant. Thy are well-known variables in the etching art and known to

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affect both the rate and quality of the etching process. Conducting routine

experimentation for the purpose of obtaining the best-etched product would optimize the

selection of a particular value. Changes in temperature, concentrations, or other

process conditions of an old process do not impart patentability unless the recited

ranges are critical, i.e., they produce a new and unexpected result. In re Aller et al., 105

USPQ 233.

Allowable Subject Matter

7. Claim 4 is objected to as being dependent upon a rejected base claim, but would

be allowable if rewritten in independent form including all of the limitations of the base

claim and any intervening claims. Prior art fails to teach an etchant consisting of Si₂F₆.

Any inquiry concerning this communication or earlier communications from the

examiner should be directed to Lynette T. Umez-Eronini whose telephone number is

703-306-9074. The examiner can normally be reached on Second Friday.

Itue

October 9, 2001

BENJAMIN L. UTECH

SUPERVISORY PATENT EXAMINER
TECHNOLOGY CENTER 1700